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| Substitute Form PTO-1449 (Modified) | U.S. Department of Commerce Patent and Trademark Office | Attorney's Docket No. 14580-034001 | Application No. 10/676,360 |
| Information Disclosure Statement by Applicant (Use several sheets if necessary) (37 CFR §1.98(b)) | | Applicant Haoren Zhuang et al. | |
| | | Filing Date September 30, 2003 | Group Art Unit 2811 |

| U.S. Patent Documents | | | | | | | |
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| Examiner Initial | Desig. ID | Document Number | Publication Date | Patentee | Class | Subclass | Filing Date If Appropriate |
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| Examiner Initial | Desig. ID | Document Number | Publication Date | Country or Patent Office | Class | Subclass | Translation | |
| | | | | | | | Yes | No |
| | AL | | | | | | | |
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| Examiner Signature | Date Considered 03/02/2005 |
| EXAMINER: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. | |